

Gp 1765

Patent
Attorney's Docket No. 015290-238

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Jeffrey HUNG et al.

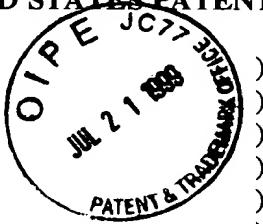
Application No.: 09/002,007

Filed: December 31, 1997

For: ETCHING PROCESS FOR ORGANIC
ANTI-REFLECTIVE COATING

Group Art Unit: 1765

Examiner: L. Vinh



REPLY TRANSMITTAL LETTER

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Enclosed is a reply for the above-identified patent application.

- [] A Petition for Extension of Time is also enclosed.
- [] Also enclosed is _____
- [] _____ statement(s) claiming small entity status
[] are also enclosed [] were submitted previously.
- [] A Request for Entry and Consideration of Submission under 37 C.F.R. § 1.129(a) is also enclosed.
- [] No additional claim fee is required.
- An additional claim fee is required, and is calculated as shown below:

RECEIVED
JUL 23 1998
TC 1700 MAIL ROOM

(11/98)

| AMENDED CLAIMS | | | | | |
|--|---------------|---|--------------|-------------|----------------|
| | NO. OF CLAIMS | HIGHEST NO. OF CLAIMS PREVIOUSLY PAID FOR | EXTRA CLAIMS | RATE | ADDT'L FEE |
| Total Claims | 21 | MINUS 20 = | 1 | x \$18.00 = | 18.00 |
| Independent Claims | 3 | MINUS 3 = | 0 | x \$78.00 = | |
| If Amendment adds multiple dependent claims, add \$260.00 | | | | | |
| Total Amendment Fee | | | | | |
| If small entity status is claimed, subtract 50% of Total Amendment Fee | | | | | |
| TOTAL ADDITIONAL FEE DUE FOR THIS AMENDMENT | | | | | \$18.00 |

[X] A claim fee in the amount of \$ 18.00 is enclosed.

[] Charge \$ _____ to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in triplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

By:


Peter K. Skiff
Registration No. 31,917

P.O. Box 1404
Alexandria, Virginia 22313-1404
(703) 836-6620

Date: July 21, 1999

(11/98)




#8/A
10
7/26/99
Patent
Attorney's Docket No. 015290-238

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)
Jeffrey HUNG et al.) Group Art Unit: 1765
Application No.: 09/002,007) Examiner: L. Vinh
Filed: December 31, 1997)
For: ETCHING PROCESS FOR ORGANIC)
ANTI-REFLECTIVE COATING)

RECEIVED
JUL 23 1999
TC 1700 MAIL ROOM

AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Official Action dated April 21, 1999, please amend the above-identified application as follows.

IN THE CLAIMS:

Please amend the claims and add new claims as follows:

CA 1
93. (Amended) The process of Claim 1, wherein the ARC is exposed by channels forming [an interconnecting network] a circuit pattern previously etched in ^{the} photoresist covering the ARC.

[Claim 4, line 2, change "essential" to --essentially--.]

AZ
10. (Amended) The process of Claim 1, wherein the plasma is generated adjacent a substrate including the ARC, the plasma generating device including a dielectric window facing the substrate and [generating device includes] an antenna outside the reaction